IN THE CLAIMS:

Please AMEND claims 31, 32 and 33 as follows.. For the Examiner's convenience, all claims currently pending in this application have been reproduced below:

1. (Previously Presented) An exposure method including plural sample shot processes to be made to a substrate and an exposure process to be made to the substrate after completion of the sample shot processes, said method comprising:

a first determining step for determining the processing order in a first sample shot process, of the plural sample shot processes; and

a second determining step for determining the processing order in a second sample shot process to be made after the first sample shot process,

wherein, in at least one of said first and second determining steps, the determination is made under a condition that an interval between a shot to be processed last in the first sample shot process and a shot to be processed first in the second sample shot process is shortened.

2. (Original) A method according to Claim 1, wherein, in said at least one determining step, positions of sample shots are also determined.

3. (Previously Presented) An exposure method including a sample shot process to be made to a substrate and an exposure process to be made to the substrate after completion of the sample shot process, said method comprising:

a first determining step for determining the processing order in the sample shot process; and

a second determining step for determining the processing order in the exposure process to be made after the sample shot process,

wherein, in at least one of said first and second determining steps, the determination is made under a condition that an interval between a shot to be processed last in the sample shot process and a shot to be processed first in the exposure process is shortened.

4. (Original) A method according to Claim 3, wherein, in said at least one determining step, positions of sample shots are also determined.

5. (Original) An exposure method including plural sample shot processes to be made to a substrate and an exposure process to be made to the substrate after completion of the sample shot processes, said method comprising:

a first determining step for determining the processing order in a first sample shot process, of the plural sample shot processes; and

a second determining step for determining the processing order in a second sample shot process to be made after the first sample shot process, in accordance with a position of a shot to be processed last in the first sample shot process.

6. (Original) An exposure method including plural sample shot processes to be made to a substrate and an exposure process to be made to the substrate after completion of the sample

shot processes, said method comprising:

a first determining step for determining the processing order in a first sample shot process, of the plural sample shot processes; and

a second determining step for determining the processing order in a second sample shot process to be made prior to the first sample shot process, on the basis of a position of a shot to be processed first in the first sample shot process.

7. (Original) An exposure method including a sample shot process to be made to a substrate and an exposure process to be made to the substrate after completion of the sample shot process, said method comprising:

a first determining step for determining the processing order in the sample shot process; and

a second determining step for determining the processing order in the exposure process to be made after the sample shot process, in accordance with a position of a shot to be processed last in the sample shot process.

8. (Original) An exposure method including a sample shot process to be made to a substrate and an exposure process to be made to the substrate after completion of the sample shot process, said method comprising:

a first determining step for determining the processing order in the exposure process; and

a second determining step for determining the processing order in the sample shot

process to be made prior to the exposure process, in accordance with a position of a shot to be processed first in the exposure process.

9. (Previously Presented) An exposure method including plural sample shot processes to be made to a substrate and an exposure process to be made to the substrate after completion of the sample shot processes, said method comprising:

a first determining step for determining the processing order in a first sample shot process, of the plural sample shot processes; and

a second determining step for determining the processing order in a second sample shot process to be made after the first sample shot process,

wherein, in at least one of said first and second determining steps, the determination is made so that a difference between a position of a shot to be processed last in the first sample shot process and a position of a shot to be processed first in the second sample shot process falls within a range of a single shot with respect to a vertical and longitudinal size in a shot layout.

10. (Previously Presented) An exposure method including a sample shot process to be made to a substrate and an exposure process to be made to the substrate after completion of the sample shot process, said method comprising:

a first determining step for determining the processing order in the sample shot process; and

a second determining step for determining the processing order in the exposure

process to be made after the sample shot process,

wherein, in at least one of said first and second determining steps, the determination is made so that a difference between a position of a shot to be processed last in the sample shot process and a position of a shot to be processed first in the exposure process falls within a range of a single shot with respect to a vertical and longitudinal size in a shot layout.

11. (Previously Presented) A device manufacturing method, comprising:

an exposure step including plural sample shot processes to be made to a substrate and an exposure process to be made to the substrate after completion of the sample shot processes, said exposure step further including (i) a first determining step for determining the processing order in a first sample shot process, of the plural sample shot processes, and (ii) a second determining step for determining the processing order in a second sample shot process to be made after the first sample shot process, wherein, in at least one of said first and second determining steps, the determination is made under a condition that an interval between a shot to be processed last in the first sample shot process and a shot to be processed first in the second sample shot process is shortened; and

a developing step for performing a development process to the substrate having been processed in said exposure step, for production of devices on the substrate.

12. (Original) A method according to Claim 11, wherein, in said at least one determining step, positions of sample shots are also determined.

13. (Previously Presented) A device manufacturing method, comprising:

an exposure step including a sample shot process to be made to a substrate and an exposure process to be made to the substrate after completion of the sample shot process, said exposure step further including (i) a first determining step for determining the processing order in the sample shot process, and (ii) a second determining step for determining the processing order in the exposure process to be made after the sample shot process, wherein, in at least one of said first and second determining steps, the determination is made under a condition that an interval between a shot to be processed last in the sample shot process and a shot to be processed first in the exposure process is shortened; and

a developing step for performing a development process to the substrate having been processed in said exposure step, for production of devices on the substrate.

14. (Original) A method according to Claim 13, wherein, in said at least one determining step, positions of sample shots are also determined.

15. (Previously Presented) A device manufacturing method, comprising:

an exposure step including plural sample shot processes to be made to a substrate and an exposure process to be made to the substrate after completion of the sample shot processes, said exposure step further including (i) a first determining step for determining the processing order in a first sample shot process, of the plural sample shot processes, and (ii) a second determining step for determining the processing order in a second sample shot process to be made after the first sample shot process, in accordance with a position of a shot to be

processed last in the first sample shot process; and

a developing step for performing a development process to the substrate having been processed in said exposure step, for production of devices on the substrate.

16. (Previously Presented) A device manufacturing method, comprising:

an exposure step including plural sample shot processes to be made to a substrate and an exposure process to be made to the substrate after completion of the sample shot processes, said exposure step further including (i) a first determining step for determining the processing order in a first sample shot process, of the plural sample shot processes, and (ii) a second determining step for determining the processing order in a second sample shot process to be made prior to the first sample shot process, on the basis of a position of a shot to be processed first in the first sample shot process; and

a developing step for performing a development process to the substrate having been processed in said exposure step, for production of devices on the substrate.

17. (Previously Presented) A device manufacturing method, comprising:

an exposure step including a sample shot process to be made to a substrate and an exposure process to be made to the substrate after completion of the sample shot process, said exposure step further including (i) a first determining step for determining the processing order in the sample shot process, and (ii) a second determining step for determining the processing order in the exposure process to be made after the sample shot process, in accordance with a position of a shot to be processed last in the sample shot process; and

a developing step for performing a development process to the substrate having been processed in said exposure step, for production of devices on the substrate.

18. (Previously Presented) A device manufacturing method, comprising:

an exposure step including a sample shot process to be made to a substrate and an exposure process to be made to the substrate after completion of the sample shot process, said exposure step further including (i) a first determining step for determining the processing order in the exposure process, and (ii) a second determining step for determining the processing order in the sample shot process to be made prior to the exposure process, in accordance with a position of a shot to be processed first in the exposure process; and

a developing step for performing a development process to the substrate having been processed in said exposure step, for production of devices on the substrate.

19. (Previously Presented) A device manufacturing method, comprising:

an exposure step including plural sample shot processes to be made to a substrate and an exposure process to be made to the substrate after completion of the sample shot processes, said exposure step further including (i) a first determining step for determining the processing order in a first sample shot process, of the plural sample shot processes, and (ii) a second determining step for determining the processing order in a second sample shot process to be made after the first sample shot process, wherein, in at least one of said first and second determining steps, the determination is made so that a difference between a position of a shot to be processed last in the first sample shot process and a position of a shot to be processed first in

the second sample shot process falls within a range of a single shot with respect to a vertical and longitudinal size in a shot layout; and

a developing step for performing a development process to the substrate having been processed in said exposure step, for production of devices on the substrate.

20. (Previously Presented) A device manufacturing method, comprising:

an exposure step including a sample shot process to be made to a substrate and an exposure process to be made to the substrate after completion of the sample shot process, said exposure step further including (i) a first determining step for determining the processing order in the sample shot process, and (ii) a second determining step for determining the processing order in the exposure process to be made after the sample shot process, wherein, in at least one of said first and second determining steps, the determination is made so that a difference between a position of a shot to be processed last in the sample shot process and a position of a shot to be processed first in the exposure process falls within a range of a single shot with respect to a vertical and longitudinal size in a shot layout; and

a developing step for performing a development process to the substrate having been processed in said exposure step, for production of devices on the substrate.

21. (Previously Presented) An exposure apparatus wherein plural sample shot processes are made to a substrate and an exposure process is made to the substrate after completion of the sample shot processes, said apparatus comprising:

first determining means for determining the processing order in a first sample shot

process, of the plural sample shot processes; and

second determining means for determining the processing order in a second sample shot process to be made after the first sample shot process,

wherein, in at least one of said first and second determining means, the determination is made under a condition that an interval between a shot to be processed last in the first sample shot process and a shot to be processed first in the second sample shot process is shortened.

22. (Original) An apparatus according to Claim 21, wherein, in said at least one determining means, positions of sample shots are also determined.

23. (Previously Presented) An exposure apparatus wherein a sample shot process is made to a substrate and an exposure process is made to the substrate after completion of the sample shot process, said apparatus comprising:

first determining means for determining the processing order in the sample shot process; and

second determining means for determining the processing order in the exposure process to be made after the sample shot process,

wherein, in at least one of said first and second determining means, the determination is made under a condition that an interval between a shot to be processed last in the sample shot process and a shot to be processed first in the exposure process is shortened.

24. (Original) An apparatus according to Claim 23, wherein, in said at least one determining means, positions of sample shots are also determined.

25. (Original) An exposure apparatus wherein plural sample shot processes are made to a substrate and an exposure process is made to the substrate after completion of the sample shot processes, said apparatus comprising:

first determining means for determining the processing order in a first sample shot process, of the plural sample shot processes; and

second determining means for determining the processing order in a second sample shot process to be made after the first sample shot process, in accordance with a position of a shot to be processed last in the first sample shot process.

26. (Original) An exposure apparatus wherein plural sample shot processes are made to a substrate and an exposure process is made to the substrate after completion of the sample shot processes, said apparatus comprising:

first determining means for determining the processing order in a first sample shot process, of the plural sample shot processes; and

second determining means for determining the processing order in a second sample shot process to be made prior to the first sample shot process, on the basis of a position of a shot to be processed first in the first sample shot process.

27. (Original) An exposure apparatus wherein a sample shot process is made to a substrate and an exposure process is made to the substrate after completion of the sample shot process, said apparatus comprising:

first determining means for determining the processing order in the sample shot process; and

second determining means for determining the processing order in the exposure process to be made after the sample shot process, in accordance with a position of a shot to be processed last in the sample shot process.

28. (Original) An exposure apparatus wherein a sample shot process is made to a substrate and an exposure process is made to the substrate after completion of the sample shot process, said apparatus comprising:

first determining means for determining the processing order in the exposure process; and

second determining means for determining the processing order in the sample shot process to be made prior to the exposure process, in accordance with a position of a shot to be processed first in the exposure process.

29. (Previously Presented) An exposure apparatus wherein plural sample shot processes are made to a substrate and an exposure process is made to the substrate after completion of the sample shot processes, said apparatus comprising:

first determining means for determining the processing order in a first sample shot

process, of the plural sample shot processes; and

second determining means for determining the processing order in a second sample shot process to be made after the first sample shot process,

wherein, in at least one of said first and second determining means, the determination is made so that a difference between a position of a shot to be processed last in the first sample shot process and a position of a shot to be processed first in the second sample shot process falls within a range of a single shot with respect to a vertical and longitudinal size in a shot layout.

30. (Previously Presented) An exposure apparatus wherein a sample shot process is made to a substrate and an exposure process is made to the substrate after completion of the sample shot process, said apparatus comprising:

first determining means for determining the processing order in the sample shot process; and

second determining means for determining the processing order in the exposure process to be made after the sample shot process,

wherein, in at least one of said first and second determining means, the determination is made so that a difference between a position of a shot to be processed last in the sample shot process and a position of a shot to be processed first in the exposure process falls within a range of a single shot with respect to a vertical and longitudinal size in a shot layout.

31. (Currently Amended) A method of ~~including~~ a first process to be ~~made~~ performed to a plurality of shots on a substrate consecutively and a second process to be ~~made~~ performed to a plurality of shots on the substrate consecutively, wherein the first ~~and second processes~~ process is to be performed ~~consecutively~~ before the second process and wherein at least the first process is a sample shot process, said method comprising:

a step of determining an order in which ~~the first process is to be made~~ at least one of the first and second processes is to be performed to the plurality of shots, ~~on the basis of~~ based on a distance between two shots to be processed consecutively by the first and second processes, respectively.

32. (Currently Amended) A device manufacturing method comprising:

a first process, ~~to be made~~ being a sample process, performed to a plurality of shots on a substrate consecutively;

a second process ~~to be made~~ performed, after the first process, to a plurality of shots on the substrate consecutively~~, wherein the first and second processes are performed consecutively~~; and

a step of determining an order in which ~~the first process is made~~ at least one of the first and second processes is to be performed to the plurality of shots ~~on the basis of~~ based on a distance between two shots to be ~~processes~~ processed consecutively by the first and second processes, respectively.

33. (Currently Amended) A device manufacturing apparatus comprising:

first process means for performing a first process ~~to be made~~, being a sample shot process, to a plurality of shots on a substrate consecutively;

second process means for performing a second process ~~to be made~~ to a plurality of shots on the substrate consecutively~~, wherein the first and second processes are performed consecutively~~ after the first process means performs the first process; and

determining means for determining an order in which at least one of the first and second ~~the first process~~ processes is ~~made~~ to be performed to the plurality of shots ~~on the basis of~~ based on a distance between two shots to be processed consecutively by the first and second processes, respectively.